

	Hits	Search Text	DBs
31	38	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (surfactant or (non\$3ionic near3 surfactant) or (amphoteric near3 surfactant) or (cationic near3 surfactant)) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant) and ((ArF near9 resist) near9 acrylic)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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33	38	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (surfactant or (non\$3ionic near3 surfactant) or (amphoteric near3 surfactant) or (cationic near3 surfactant)) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant or (surface near9 active)) and ((ArF near9 resist) near9 acrylic)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB